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Courses Taught : <ul style="list-style-type: none"> □ Removable Partial Denture Technology □ Dental Morphology □ Dental Materials Science
Professional Fields : <ul style="list-style-type: none"> □ Removable Prosthodontics □ Dental Technology □ Dental Materials
Research Interests : <ul style="list-style-type: none"> □ Materials Science □ VHF Plasma
Representative Publication in 5 Years : Journal Articles : 1. K.-C. Chen, K.-F. Chiu, C.-F. Chen, C.-Y. Lien, Y.-J. Tsai, T.-K. Lien, F. Matsunaga, M. Tanaka, K. Ogiwara, K. Uchino, and Y. Kawai, "Observation of bi-Maxwellian distributions in a H ₂ plasma produced by a narrow gap VHF discharge", <i>Plasma Process. Polym.</i> vol. 13, 6, pp. 584-587, June, 2016. (SCI,EI) 2. K.-C. Chen, C.-F. Chen, C.-Y. Lien, K.-F. Chiu, J.-B. Shi, Y.-J. Tsai, T.-K. Lien, K. Ogiwara, K. Uchino, and Y. Kawai, "Axial distribution of a VHF H ₂ plasma produced by a narrow gap discharge", <i>Jpn. J. Appl. Phys.</i> vol. 55, pp. 01AH01-1-01AH01-5, January, 2016. (SCI,EI) 3. K.-C. Chen, K. Ogiwara, K.-F. Chiu, L.-W. Su, K. Uchino, and Y. Kawai, "Two-dimensional simulations of a VHF H ₂ plasma for different discharge gaps and gas pressures", <i>Jpn. J. Appl. Phys.</i> vol. 55, pp. 07LD01-1-07LD01-6, July, 2016. (SCI,EI) 4. K.-C. Chen, K.-F. Chiu, C.-F. Chen, C.-Y. Lien, Y.-J. Tsai, T.-K. Lien, K. Ogiwara, K. Uchino, and Y. Kawai, "Mechanism of VHF H ₂ plasma production at high pressures", <i>Jpn. J. Appl. Phys.</i> vol. 55, pp. 06HA02-1-06HA02-6, June, 2016. (SCI,EI) 5. K.-C. Chen, K.-F. Chiu, K. Ogiwara, L.-W. Su, K. Uchino, and Y. Kawai, "Study of spatial profiles of capacitively coupled VHF H ₂ plasma by simulation", <i>Jpn. J. Appl. Phys.</i> vol. 56, pp. 01AC05-1-

01AC05-8, January, 2017. (SCI,EI)

Conference Papers :

1.

K.-C. Chen, K.-F. Chiu, K. Ogiwara, L.-W. Su, K. Uchino, and Y. Kawai, “Two-dimensional simulations of a VHF H₂ plasma for different discharge gaps”, 68th Gaseous Electronics Conference (GEC)/9th International Conference on Reactive Plasmas (ICRP), October, 2015, vol. 60, pp. 82 (LW1 00027), American Society Applied Physics. Hawaii, U.S.A.

2.

K.-C. Chen, C.-F. Chen, C.-Y. Lien, K.-F. Chiu, J.-B. Shi, Y.-J. Tsai, T.-K. Lien, K. Ogiwara, K. Uchino, and Y. Kawai, “Mechanism of a VHF H₂ plasma production at high pressures”, 37th International Symposium on Dry Process (DPS), November, 2015, pp. 113-114 (p-26), Japan Society Applied Physics. Awaji Island, Japan.

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